

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant	:	Washio et al.
Appl. No.	:	10/560,155
Filed	:	December 9, 2005
For	:	DEVELOPER COMPOSITION FOR RESISTS AND METHOD FOR FORMATION OF RESIST PATTERN
Examiner	:	Le, Hoa Van
Group Art Unit	:	1752

SUBMISSION WITH RCE

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

In response to the final Office Action mailed **January 18, 2007**, and the Advisory Action mailed **April 26, 2007**, Applicants respectfully request consideration of the following amendments and remarks:

**Amendments to the Claims** are reflected in the listing of claims which begins on page 2 of this paper.

**Remarks/Arguments** begin on page 4 of this paper.